Electronic Supplementary Material (ESI) for Journal of Materials Chemistry C.

Supplementary Information

The Influence of surface topography on the field emission of nanostructured copper oxide thin films grown by oblique incidence deposition.

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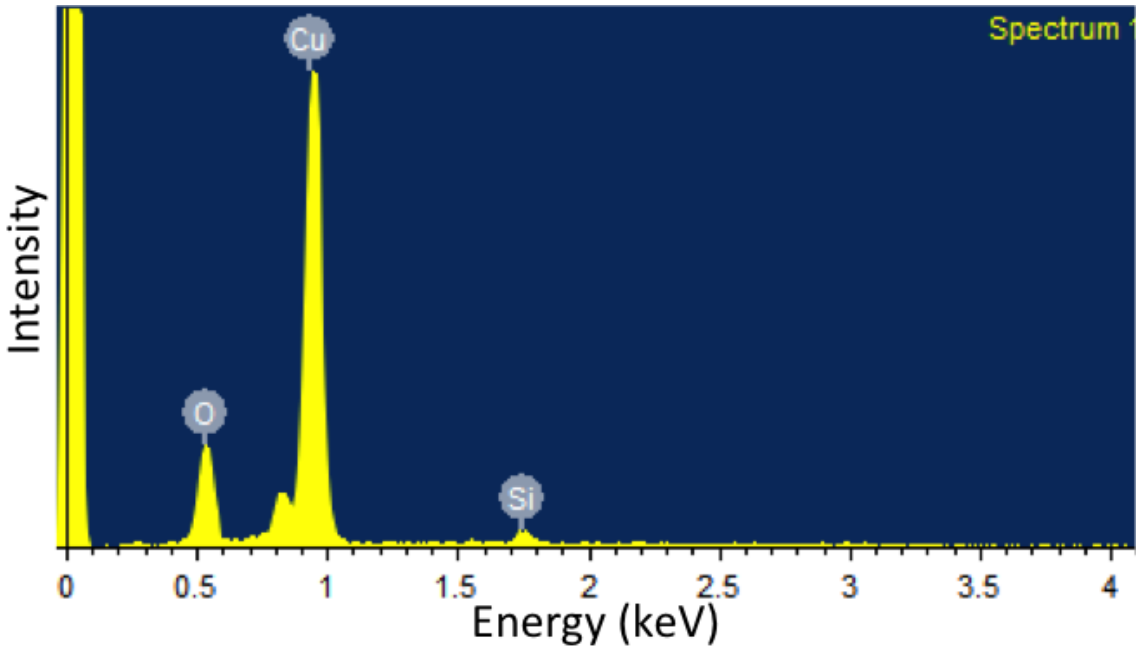
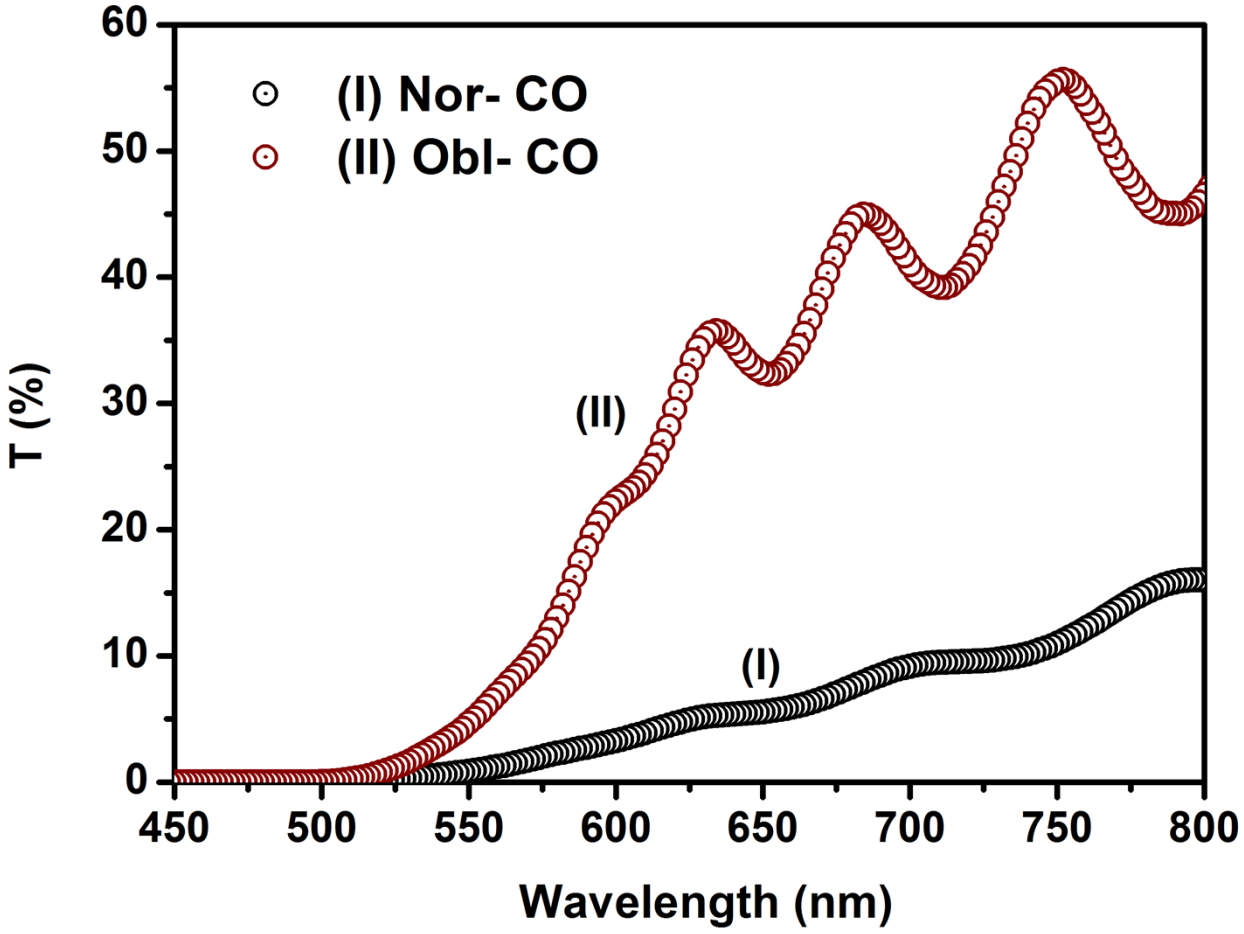
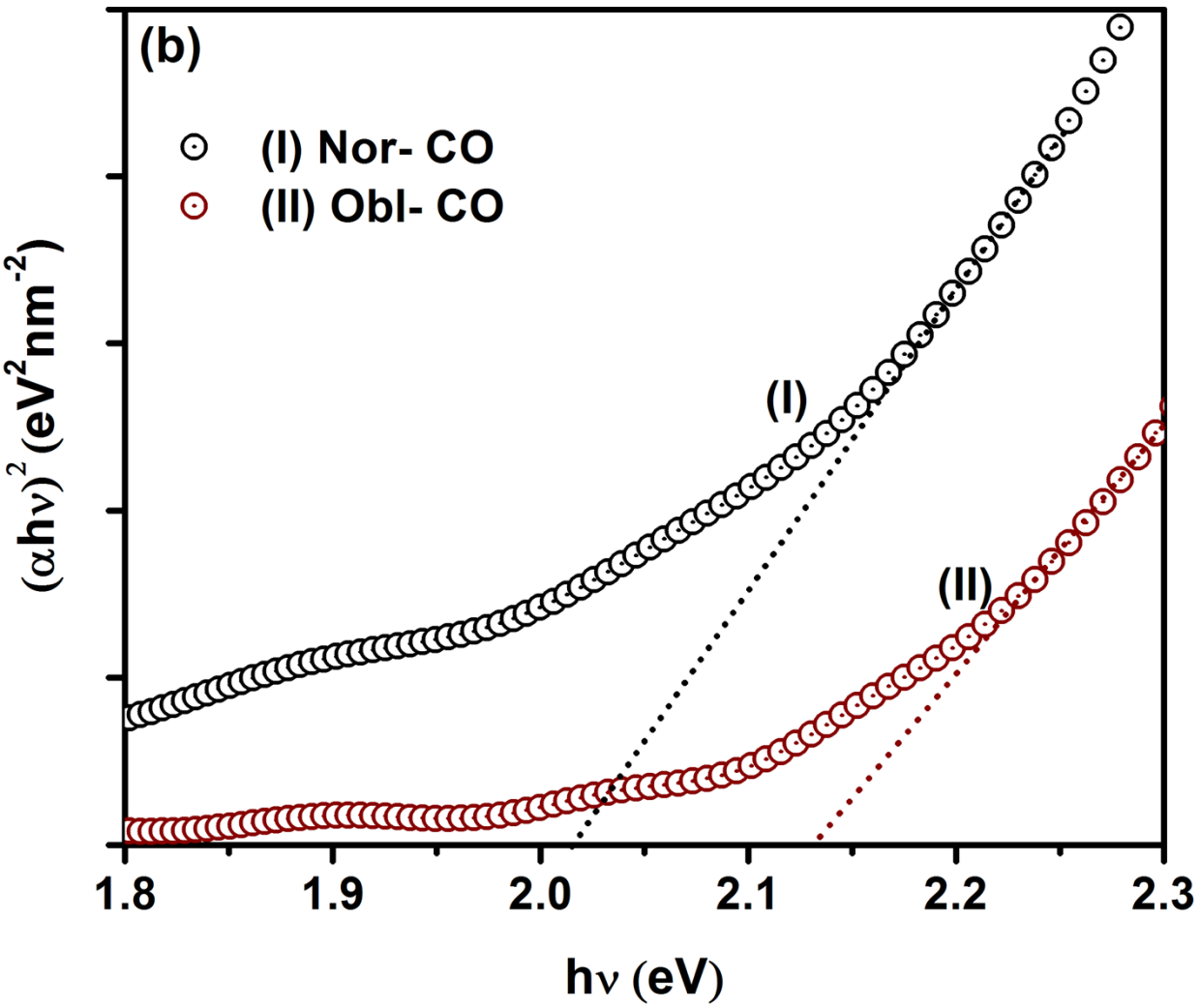


Figure S1: Representative EDX spectra of Obl-CO



S2: Transmittance plot of Nor-CO and Obl-CO



S3: Tauc plot of Nor-CO and Obl-CO

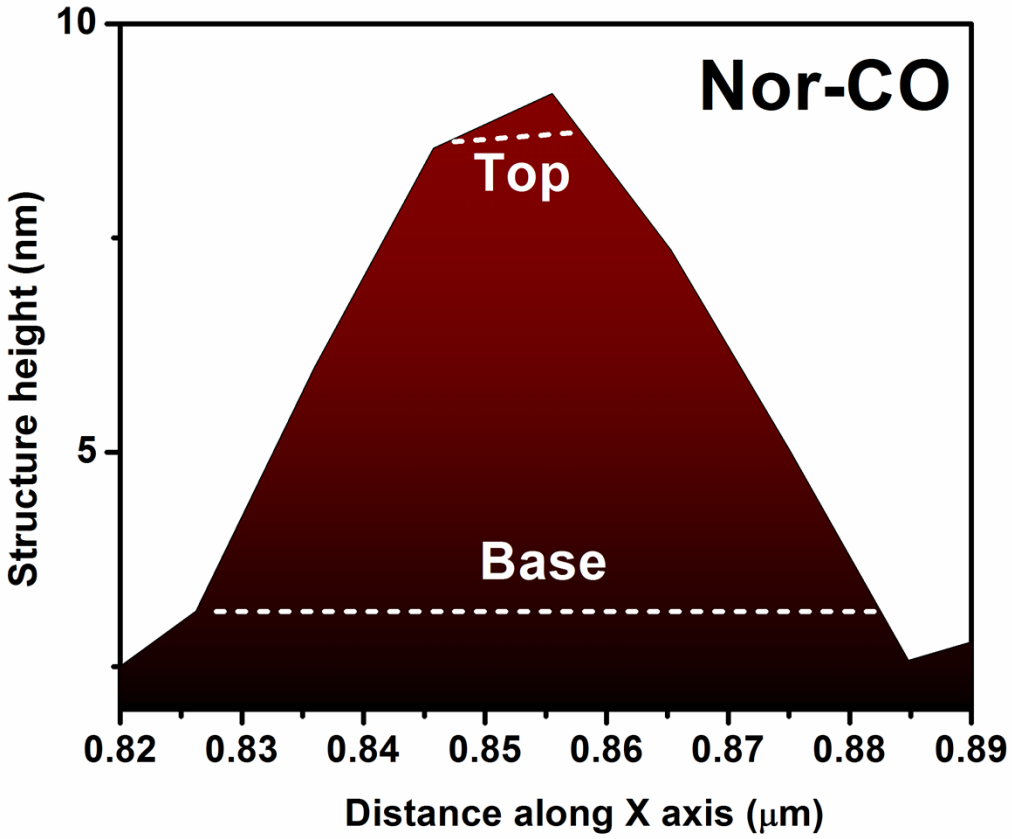


Figure S4: Line profile of Nor-CO

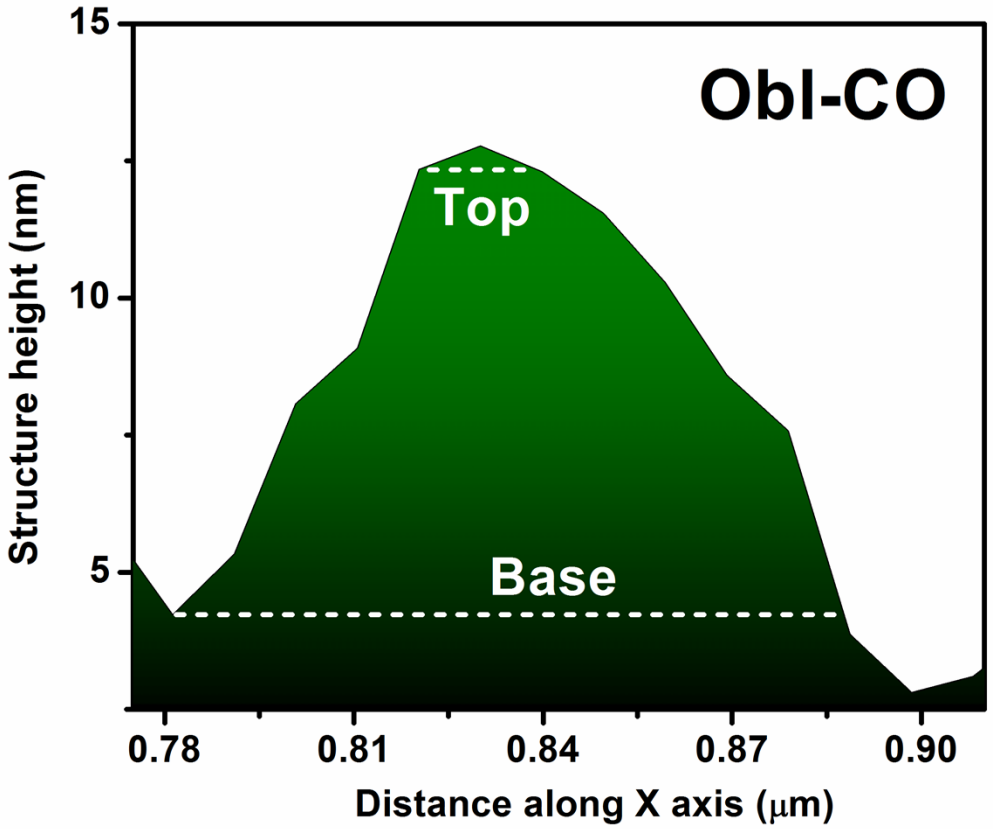


Figure S5: Line profile of Obl-CO

Table-I

Field emitting materials	Turn-on field (V/μm)	Enhancement factor (β)
[110] oriented film of Cu_2O with regular octahedral crystals[a]	9.6	-
Micro-nano porous Cu_2O cubic crystals[b]	3.1	2365
Cu_2O-ZnO heterojunction nanobrush[c]	6.5	-
Vertically oriented CuO nanowire films[d]	3.5	-
O_2 and CF_4 plasma-treated CuO nanowires[e]	3.0	-
Hybrid CuO/ZnO nanorod[f]	3.2	-
Vertically Aligned $Cu_2O_{1-\delta}$ Nanostructure[g]	0.8	-
Nanopine shaped ternary compound of Cu_2O-TiO_2 –ZnO[h]	2.8	-
Highly oriented cupric oxide (CuO) nanoknife arrays[i]	0.9	-
Nanopins of ZnO[j]	1.9	657
WO_2 Nanowire Arrays[k]	1.36	-
WO_3 Nanowire Arrays[l]	4.3	-
TiO_2 nanowire array[m]	13	391
SnO_2 nanowhisker[n]	1.37	-
Fe_2O_3 nanowires[o]	3.3	-
Cu_2O pure block[p]	6.18	-
Copper oxide thin film deposited by oblique angle sputter deposition (this work)	1.3	5144

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